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INFORMATION DISCLOSURE

STATEMENT BY APPLICANT

FILING DATE

January 14, 2002

ATTORNEY'S DKT NO.

APPLICATION NO.

10/043,190

APPLICANT

Hiroshi NOGAMI

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January 14, 2002

1744

U.S. PATIENT DOCUMENTS U.S. Patent Document Date of Publication Kind Code Name of Patentee or Applicant Examiner (MM-DD-YYYY) Initials Number (if known) of Cited Document 06-12-2001 6,246,396 **B1** Nogami FOREIGN PATENT DOCUMENTS Foreign Patent Document Date of Publication Kind Code Translation Examiner (MM-DD-YYYY) Country Yes (if known) Initials Number 08-04-1995 7-201749 Japan 2837087 Japan 10-09-1998 NON PATENT LITERATURE DOCUMENTS Include name of author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), Examiner Initials publisher, city and/or country where published. Shingo KADOMURA et al., "ANISOTROPIC ETCHING USING DEPOSITION OF SULFUR, Sony Corporation, Semiconductor World, January 1993, pp. 1-11, and translation Ken FUJITA et al., "X-RAY PHOTOELECTRON SPECTROSCOPIC STUDIES ON PYROLYSIS OF PLASMA-POLYMERIZED FLUOROCARBON FILMS ON SI", Jpn. J. Appl. Phys. volume 34 (1995), pp. 304-306, Part 1, NO. 1, January 1995 Robert C. REID et al., "THE PROPERTIES OF GASES AND LIQUIDS", McGraw-Hill, Inc., Appendix B, Index. 1987 Byron BIRD et al., "TRANSPORT PHENOMENA", Jon Wiley & Sons, pp. 508-509 and 512-513 Riccardo d'AGOSTINO et al., "PLASMA ETCHING OF Si and SiO2 in SF6-O2 MIXTURES", J. Appl. Phys. 52(1), January 1981, pp. 162-167 Date Examiner Considered Signature

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SHEET 1 OF 1

ATTORNEY'S DKT NO. 001425-117 **APPLICANT** Hiroshi Nogami FILING DATE January 14, 2002

APPLICATION NO.
10/043,190

GROUP
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